

L Number	Hits	Search Text	DB	Time stamp
1	1572	(silicon silane disilane TEOS tetraethylorthosilicate (tetraethyl adj orthosilicate) (tetraethylortho adj silicate) (tetra adj ethyl adj ortho adj silicate) TMOS tetramethylorthosilicate (tetramethyl adj orthosilicate) (tetramethylortho adj silicate) (tetra adj methyl adj ortho adj silicate)) near20 ((hydrogen adj peroxide) ("H.sub.2" adj "O.sub.2"))	USPAT; EPO; JPO	2003/04/25 17:56
5	6636	(ratio percent percentage "%") near5 ((hydrogen adj peroxide) ("H.sub.2" adj "O.sub.2"))	USPAT; EPO; JPO	2003/04/25 17:57
9	331	((silicon silane disilane TEOS tetraethylorthosilicate (tetraethyl adj orthosilicate) (tetraethylortho adj silicate) (tetra adj ethyl adj ortho adj silicate) TMOS tetramethylorthosilicate (tetramethyl adj orthosilicate) (tetramethylortho adj silicate) (tetra adj methyl adj ortho adj silicate)) near20 ((hydrogen adj peroxide) ("H.sub.2" adj "O.sub.2"))) and ((ratio percent percentage "%") near5 ((hydrogen adj peroxide) ("H.sub.2" adj "O.sub.2")))	USPAT; EPO; JPO	2003/04/25 17:57
13	147	((silicon silane disilane TEOS tetraethylorthosilicate (tetraethyl adj orthosilicate) (tetraethylortho adj silicate) (tetra adj ethyl adj ortho adj silicate) TMOS tetramethylorthosilicate (tetramethyl adj orthosilicate) (tetramethylortho adj silicate) (tetra adj methyl adj ortho adj silicate)) near20 ((hydrogen adj peroxide) ("H.sub.2" adj "O.sub.2"))) same ((ratio percent percentage "%") near5 ((hydrogen adj peroxide) ("H.sub.2" adj "O.sub.2")))	USPAT; EPO; JPO	2003/04/25 17:57
17	93857	\$5CVD (chemical adj vapor adj deposit\$3)	USPAT; EPO; JPO	2003/04/25 17:58
21	60	((silicon silane disilane TEOS tetraethylorthosilicate (tetraethyl adj orthosilicate) (tetraethylortho adj silicate) (tetra adj ethyl adj ortho adj silicate) TMOS tetramethylorthosilicate (tetramethyl adj orthosilicate) (tetramethylortho adj silicate) (tetra adj methyl adj ortho adj silicate)) near20 ((hydrogen adj peroxide) ("H.sub.2" adj "O.sub.2"))) same ((ratio percent percentage "%") near5 ((hydrogen adj peroxide) ("H.sub.2" adj "O.sub.2")))) and (\$5CVD (chemical adj vapor adj deposit\$3))	USPAT; EPO; JPO	2003/04/25 17:58